ZA4000 Series









Taking Hitachi Atomic Absorption Spectrophotometers into a Next Stage

ZA4000 Series

Hitachi atomic absorption spectrophotometers have undergone a further evolution with upgrades to Hitachi's polarized Zeeman correction method technology, a unique technology that pioneered an era in spectrophotometry.

Hitachi offers high-precision background correction and high-sensitivity measurement by employing the polarized Zeeman correction method alongside the dual detector method.

The addition of a new rapid sequential mode* (supports the flame method) makes it possible to perform even higher throughput analysis, allowing for fast, precise, and highly reproducible measurements in a variety of fields, including research and quality management.

* A mode that sequentially analyzes multiple elements

Polarized Zeeman Correction Method, Dual Detector Method

Baseline stability
Offers high-sensitivity measurement

Multi-elements Measurement

Flame

Voice guidance function
Auto start function

Graphite Furnace

Diagnosis system for low concentration analysis

Automatic bump detection function

Reduced contamination with isolated atomizer unit

Software

Real-time display of atomizer profiles

Unwavering Performance

Cumulative number of installed units >10,000





Environment



Food

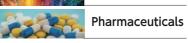


Energy



Materials

Plating



• Analysis of toxic metals in environmental water (sea water, river water) and factory wastewate

Analysis of toxic metals in soil (extracted liquids, eluates)

 \bullet Analysis of toxic metals, mineral components, and sodium (salt content) in foods and drinks

Analysis of toxic metals in animal feed

Analysis of lead in gasoline

 \bullet Analysis of main component metals and trace metals in lithium ion battery materials

• Analysis of main component metals in plating liquid

Analysis of metal impurities in plating liquid

Analysis of impurities and toxic metals in paint

• Analysis of plasticizers (metals) in materials

• Evaluation of residual amounts of catalyst metals in pharmaceuticals

Evaluation of residual amounts of toxic metals in pharmaceuticals

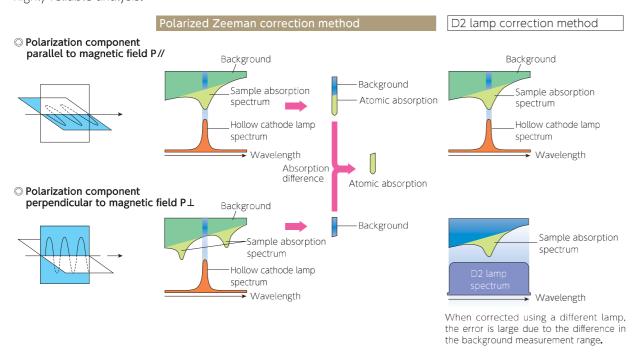




Polarized Zeeman Correction Method

Background Correction Using Only Hollow Cathode Lamp

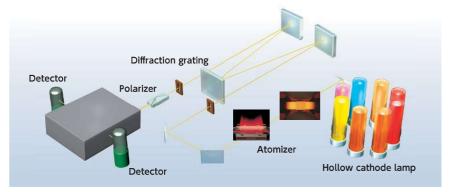
The polarized Zeeman correction method, which uses a permanent magnet, provides a stabilized baseline, suppresses the effects of coexisting materials that have absorption of adjacent wavelengths, and facilitates highly reliable analysis.

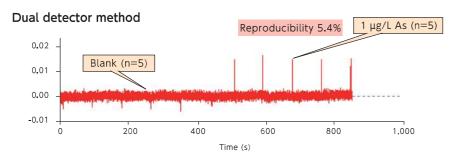


Dual Detector Method

Increases the Amount of Sampled Light and Reduces Noise

The dual detector method, by which the sample light and reference light are sampled by independent detectors, reduces the baseline noise. The two lights are also detected simultaneously, which increases the accuracy of corrections.

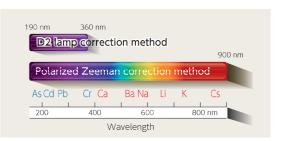




Wide Background Detection Range

All Elements are Covered by the Polarized Zeeman Correction Method

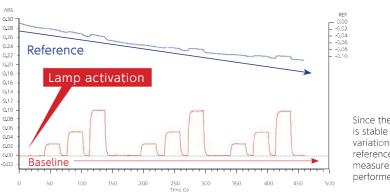
Background correction can be performed for elements that have absorption in the ultraviolet range or visible range. The polarized Zeeman correction method is one choice of correction method, and has the advantage that it does not need to be selected for each element. It can also correct elements that cannot be corrected by the D2 lamp correction method, such as sodium and potassium.



Baseline Stability

The Baseline is Stable Immediately after Lamp Activation

The polarized Zeeman correction method performs correction using a single line from a hollow cathode lamp, providing a stable baseline regardless of variations in lamp brightness. Even if there are many elements to measure, this baseline stability leads to reduced lamp stabilization time and faster analysis speed.

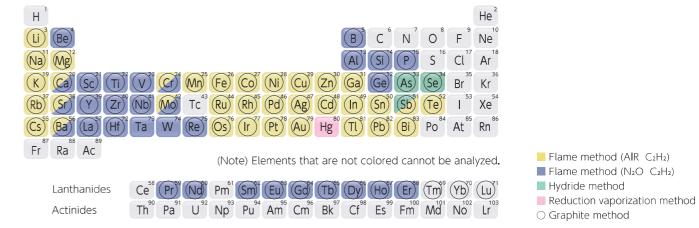


Since the baseline is stable despite variations in the reference signal (blue), measurement can be performed immediately.

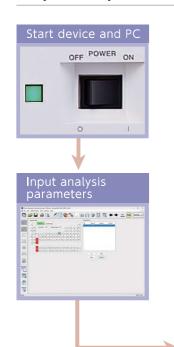
Support for Multiple Elements

The Polarized Zeeman Correction Method Can Also Be Used with Measurements Using Accessories

The polarized Zeeman correction method and dual detector method are employed for measurements using any of the flame method, graphite method, or hydride method.



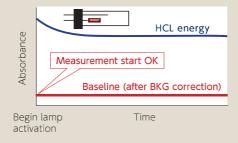
Rapid Sequential Mode



Lamp Baseline Stability Through Polarized activation Zeeman Correction Method

With the polarized Zeeman correction method, which performs measurement using only a hollow cathode lamp, measurement can start without waiting for the lamp stabilization time. Even if multiple element lamps are activated at the same time, since the baseline is stable regardless of the type of lamp, this correction method can exploit the advantages of sequential measurement.





Rapid Sequential Measurement

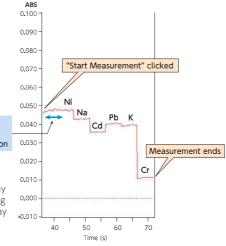
Sequential Measurement of Multiple Elements with a Single Sample Injection

When 6 elements are measured in rapid sequential mode, the absorbances of the 6 elements are measured sequentially while the diffraction grating is driven at high speed, with only one sample injection needed. The measurement results for the 6 elements can be output simultaneously by performing this measurement repeatedly.

The profile on the right is the atomizer profile of each of the 6 elements when measured with a data sampling time of 5 seconds.

Stabilization time (delay time) after sample injection

Note: The profile display mode was set to "during measurement" to display the profile only during



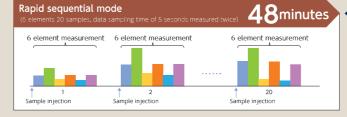
Increased Measurement Speed with Newly Developed Diffraction Grating Drive Mechanism

High-speed measurement has been realized by employing a new optical system that increases the drive speed of the diffraction grating.

A maximum of 12 elements can be sequentially measured by activating 4 hollow cathode lamps at the same time.







Approx. 30% reduction

- Note: 1. Measurement time is the time from lamp on until measurement ends.

 2. Measurement time varies depending on
 - 2. Measurement time varies depending on analysis parameters.

Reduced Running Costs

Reduced Running Costs with Fast Startup and Short Measurement times

Using the polarized Zeeman correction method for rapid baseline stability and the rapid sequential mode, the lamp-on time and flame operation time can be reduced, thereby reducing running costs.

Worker-Friendly Process Flow

Reduced Repetitive Sample Injection Tasks

Since the rapid sequential mode measures multiple elements with a single sample injection, there is no need to frequently change the sample. For example, measuring 6 elements in 20 samples would normally require 120 sample injections. However, with the rapid sequential mode, the measurement is completed with only 20 injections.

Tandem (Flame and Graphite Flame Model Rapid Sequential Flame Model Furnace) Model **ZA4000 ZA4300**

ZA4000 ZA4300 ZA4800

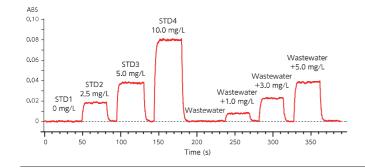
ZA4800

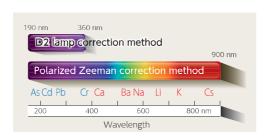
Background Correction by Polarized Zeeman Correction Method that is Unique to the Technology of Hitachi

Providing High-Precision Background Correction Across All Wavelengths

High-precision background correction can be performed, even for elements like cesium, which has a long absorption wavelength (852.1 nm).

O Analysis of cesium in wastewater





Analysis of cesium in wastewater

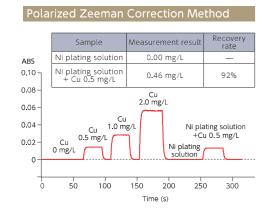
Sample name	Measurement result (mg/L)	Recovery rate (%)
Wastewater*	ND(≤ 0.04)	_
Wastewater+1.0 mg/L	1.06	106
Wastewater+3.0 mg/L	3.04	101
Wastewater+5.0 mg/L	5.15	103

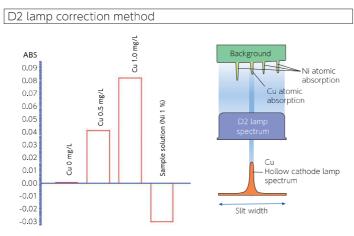
*Japan Environmental Measurement and Chemical Analysis Association JEMCA 0005-1

Providing High-Precision Analysis Even for High-Matrix Samples

With the polarized Zeeman correction method, measurement is possible even if background absorption exists at nearby wavelengths.

Analysis of copper in nickel plating solution (comparison of measurements depending on differences in correction methods)





High-Sensitivity Analysis

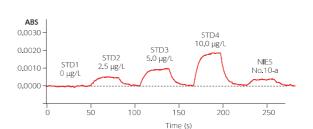
ZA4000 ZA4300 ZA4800

Achieving High-Sensitivity Analysis with Stable Baseline

A stable baseline is provided by the polarized Zeeman correction method, and low concentration analysis can be performed with high-sensitivity measurement without using any additional accessories.

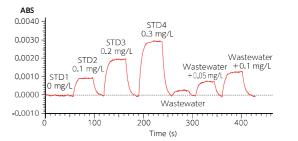
O Analysis of cadmium in brown rice

Sample	Certified value (µg/g)	Measurement result (μg/g)			
NIES No.10-a	0.023 ± 0.003	0.021			
Note: Sample measured at 10-fold dilution					



O Analysis of lead in wastewater

Sample	result (mg/L)	rate (%)
Wastewater (Certified value: 0.030 mg/L)	0.031	_
Wastewater + 0.05 mg/L	0.079	96
Wastewater + 0.1 mg/L	0.131	100



Supporting Measurement of Organic Solvents ZA4000 ZA4800 ZA4800

Providing Stable Analysis

Even for solutions based on organic solvents, the polarized Zeeman correction method is able to provide a stable baseline.

Even for the measurement of lead in a xylene base, the absorbance of the standard solution measured two times in a row is a good match even without making Auto-Zero adjustments.

O Measurement of lead in xylene base 0.20 0.18 0.16 0.14-0.12 0.10

0.08 ----- 10.0 mg/L Pb 0.06 0.04 0.02 0.00 -0.02

Oil-based standard solution diluted in xylene.

Auto-Start and Voice Guidance

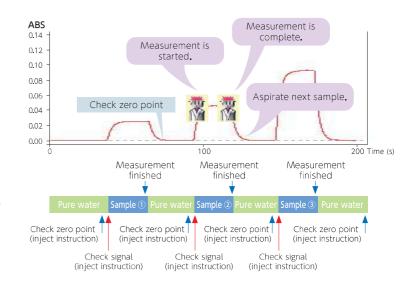
200 Time (s)

ZA4300 ZA4800

Analysis Assistance Software

Drift is suppressed by the polarized Zeeman correction method, and the absorbance returns to near zero during blank absorption. Because of this, measurement can be performed by automatically determining the timings of sample injection, measurement start, and measurement end. The timing for switching out samples is notified by voice guidance.

This makes it possible for even those new to atomic absorption spectrophotometry to perform measurements stress-free.



Increased Usability with Switches on the instrument front

Enables Operation without Changing Positions

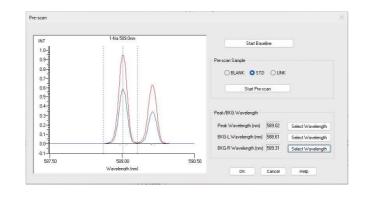
The front panel of the instrument is equipped with "Start Measurement" and "Auto-Zero" buttons, making it possible to perform a series of measurements without needing to operate the computer. By reducing the working range, this reduces the risk of knocking over samples or taking the wrong sample, making it easy to perform safe and secure measurements.



Emission Background Correction Function ZA4000 ZA4800 ZA4800

Background is Also Corrected in Emission

The background intensity is measured near the measurement wavelength, and the background is corrected using the base emission intensity for each sample, making it possible to perform accurate measurements.



Environmental Considerations

ZA4000 ZA4300 ZA4800

Environmentally Friendly Analysis Using Water Saving and Power Saving Modes

When the standby time exceeds some fixed time, the cold water supply is stopped in water saving mode and the hollow cathode lamp is turned off in power saving mode.

Water saving and power saving modes can be selectively enabled or disabled.

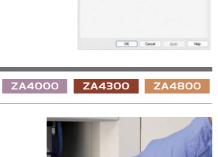
Note: Water saving mode is installed in the ZA4000 model.



Safety

Safety Functions for Safe Analysis

- Ploys an aluminum-made manifold-type gas control unit
- Gas leak check on flame ignition
- Automatic stop of gas supply when flame extinguished
- Prevention of backfire caused by supporting gas buffer tank at power failure
- Monitoring by flame sensor
- Pressure monitoring of fuel gas and auxiliary gas
- High temperature burner interlock function
- Burner drain liquid level monitoring
- Cooling water flow monitoring
- Burner head cooling by cool water



0

incorrect operation

Flame Accessories

High-Temperature Burner Head Hose Set

Used for measurement of elements that have a high dissociation energy such as Al, B, Be, Ge, La, Nb, Si, Ta, Ti, V, W, and Zr. Should be used with a nitrous oxide -acetylene

Optical path length: 5 cm. Material: Titanium.

Includes dedicated hose set.

When using the hydride

Heated Quartz Cell with Support

formation system, it is mounted above the burner and heated using an air-acetylene flame.

Note: There is also a type without the cell holder [7J0-8861].

High Salt Burner Head

Used when measuring high

salinity samples. Use with

Optical path length: 10 cm.

Optical path length: 10 cm.

an air-acetylene flame.

Material: Titanium.

Material: Titanium.



○ Time change in measurement of

Pb in 10% NaCl

Abs 0.008

0.004

0.002

0.000

Glass Atomizer Set

This is also able to measure samples that contain aqua regia without corrosion.

Material: Glass only.



SSC-230 Flame Autosampler

Samples the target solution sample automatically using a random access sampler to reduce measurement time and minimize sample consumption.

- Can be loaded with up to a maximum of 80 samples.
- The random access function can be configured for each element, and automatic multi-elements measurement can be performed on up to 12 elements.
- Automatically extinguishes the flame after the measurement is complete and the burner chamber is clean.



PFA Disperser

The PFA disperser is used when analyzing samples that contain hydrofluoric acid.



100 150 180 Time (s)

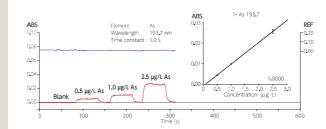
HFS-4 Hydride Formation System

- Elements such as As and Se can be analyzed with high sensitivity by using sodium borohydride.
- Employs a 4-rotor peristaltic pump that enables automatic mixing of potassium iodide.
- Provides a stable baseline using the polarized Zeeman correction method

Elements to measure: As, Sb,



O Measurement of arsenic standard solution



Micro-Sampling Kit

Enables flame measurement with samples of less than 0.5 mL. Prevents sample solutions from clogging the burner



Measurement of copper standard Element : Cu Wavelength: 324.8 nm Time constant: 1.0 s Sample volume: 100 µl 4 mg/L Cu 0.04-2 mg/L Cu mg/L Cu

Mercury Analyzer

Enables a reducing agent to be added to the sample solution to vaporize the mercury, and performs high-sensitivity analysis.

SnCl₂ is used as the reagent.

Note: Drying agent dehumidification type.



Tandem (Flame and Graphite Furnace) Model

ZA4000

Graphite Model **ZA4700**





Background Correction Using Polarized Zeeman Correction Method Unique to Hitachi technology

ZA4000 ZA4700

Performing Background Correction in All Stages

The background is monitored in all measurement stages (drying, ashing, atomization, cleaning, and cooling) by the polarized Zeeman correction method using a permanent magnet.

Sample injection

Sample is injected inside the cuvette by the autosampler

Ory

Removes the moisture contained in the sample

Ash

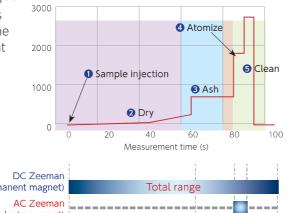
Removes coexisting materials contained in the sample

4 Atomize

Atomizes the target element (absorbance measurement)

Heats the cuvette temperature to the maximum to remove measurement residue

Cuvette temperature change during measurement



Automatic Bumping Detection Function

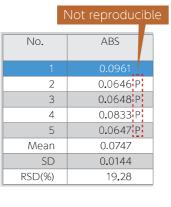
ZA4000 ZA4700

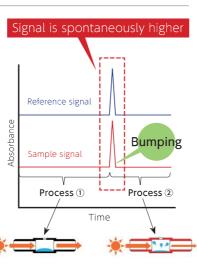
Atomization only

Ability to Verify Whether a Bump Occurred Even After Measurement

Bumps are detected by monitoring the background and absorbance signals during dry stage.

Measurement data values with a possibility of having been taken during a bump are marked with a "P".



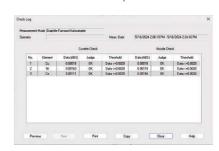


Diagnosis system for low concentration analysis NEW

ZA4000 ZA4700

Easy Confirmation of Contamination During Low Concentration Analysis

When low concentration analysis is performed using the graphite method, the correct analysis values cannot be obtained if there is any contamination in the electric furnace or sample transport fluid system. However, by using the "check for graphite atomizer contamination" function, which automatically performs the sequence of checking for contamination in the electric furnace including the cuvette and the auto sample transport fluid path, even those new to the analysis can easily perform low concentration analysis. Furthermore, the contamination state of the instrument can be determined quickly, which reduces the time needed for contamination checks.



Built-in Autosampler

ZA4000 ZA4700

Analysis is Assisted by a High Function Autosampler

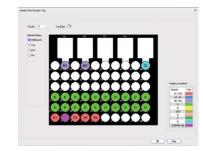
- Can hold a maximum of 60 samples.
- Measures the sample specified by the random access function.
- Up to a maximum of 100 μL of sample can be injected in steps of 1 μL.
- Injection speed can be set to one of 5 values.
- Dilution (aliquot) of standard solution using an automatic dilution
- Can also handle organic solvent samples such as methanol and MIBK.
- Can use 96 microplates (optional accessory).

Autosampler Cup Layout Guidance NEW

ZA4000 ZA4700

Check the Layout of Samples at a Glance

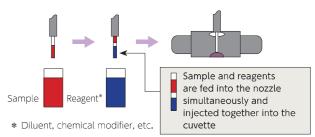
The sample rack display screen can be displayed by changing the sample colors for standard solutions, chemical modifiers, etc. depending on the configured autosampler settings. The risk of incorrectly placing samples can be reduced by comparing this visual guide with the sample rack. This makes it possible to check the placement positions of samples at a glance, even for those new to the analysis.



Batch Injection of Multiple Samples (Sequential Injection)

Even Low-Volume Samples are Injected with Good Reproducibility

The injection precision can be improved by sequentially injecting several microliters of sample together with chemical modifiers and diluent.







Temperature Program Development Function

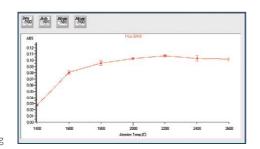
ZA4000 ZA4700

Assistance with Temperature Profile Creation

The absorbance can be measured by changing the drying, ashing, and atomization temperatures in a stepwise manner. The optimal temperature profile parameters can then be generated based on these results.

This process considers both the absorbance and its variation (relative standard deviation) at each stage.

Note: The graph on the right is a graph of atomization temperature for checking

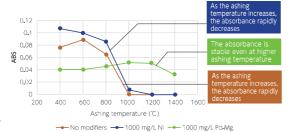


Addition of Chemical Modifiers

ZA4000 ZA4700

Automatic Addition of 4 Types of Chemical Modifiers

A maximum of 4 types of chemical modifiers can be automatically added by the autosampler. The order of addition can also be configured to before or after the sample. For example, the ashing temperature can be set higher by using a palladium-magnesium chemical modifier during the measurement of lead to suppress the effects of coexisting materials.



Effect of chemical modifiers on lead

Dustproof Cover

ZA4000 ZA4700

Split Dustproof Cover to Protect from Contamination

Dustproof covers are fitted on the graphite furnace and top of the autosampler to protect against dust and debris in the laboratory. Furthermore, the covers enable access to the autosampler side, which is frequently opened and closed, as a further measure against contamination of the atomizer.



LED Spot Light for Furnace

ZA4000 ZA4700

Ensures Visibility When Replacing the Cuvette

An LED spot light is used to illuminate the graphite furnace. This improves visibility when adjusting the autosampler nozzle position and when replacing the cuvette, facilitating easier maintenance.

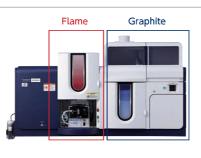


Independent Atomizer

ZA4000

Independent Flame and Graphite Atomizers **Reduce Contamination**

Contamination originating from samples measured by the flame method can be reduced when performing graphite measurement for analysis of low concentrations by making the atomizer independent of the flame measurement, which is used for analysis of high concentrations.



Graphite Furnace Accessories

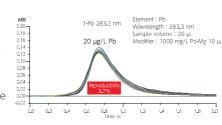
Cuvettes	vettes						
Name	Application / Temperature / I njection Volume	Shape	Features	Suitable fields			
Pyro Tube CIIHR [7J1-8540]	Up to 2,800 °C Up to 100 µL 10 per box		High atomizer temperature general- purpose cuvette Reduces formation of carbides	 Suitable for samples in all fields (Particularly optimized for high-sensitivity analysis) 			
Pyro Tube DII HR [7J1-8550]	For twin injection Up to 2,800 ℃ Up to 100 µL 10 per box		Reduces diffusion of sample solution and increases measurement accuracy through dispersion injection High atomizer temperature general-purpose cuvette Reduces formation of carbides	Suitable for samples in all fields			
Pyro Tube HR [7J0-8880]	Up to 2,800 °C Up to 100 μL 10 per box		High atomizer temperature general-purpose cuvette Reduces formation of carbides Recommended for measuring high melting point elements such as Mo and V	all fields (Particularly optimized			
Graphite Tube HR [7J0-8885]	Up to 2,800 ℃ Up to 50 µL 10 per box		Elements that require reducing nature	• Can be used in all fields			
Cup-type cuvette HR [7J0-8890]	Up to 2,100 °C Up to 50 μL 10 per box		Large sample injection port with structure to prevent diffusion of sample solution Samples that contain a lot of organic material Useful for samples that foam at the Dry Stage Increases reproducibility	Organic samples			
OMEGA Platform Tube HR [7J0-8897]	Reduces chemical interference Up to 2,600 °C Up to 100 µL 10 per box	Platform	 Single piece with Ω-shaped platform inserted into the tube in advance The tube interior reaches thermal equilibrium by heating of the sample by radiative heating before atomization, reducing interference with coexisting materials 	High-matrix materials			
Ring (4PCS/SET) [7J1-8900]	Rings for attaching cuvette to the electrodes 4 per box		● Support brackets	_			

Note: For high-concentration samples, Graphite Tube C II HR [7J1-8545] is also available, which offers reduced sensitivity compared to Graphite Tube HR [7J0-8885].

OMEGA Platform Tube HR

Makes it possible to perform high-precision analysis even for samples with a lot of coexisting materials. Interference from coexisting materials can be reduced by performing atomization of samples in a state of thermal equilibrium with the atmosphere inside the cuvette. This reduces interference from the matrix and makes it possible to perform high-precision analysis.

O Reproducibility of lead in 1% nickel solution (n=10)

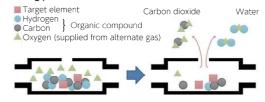


Alternate Gas Unit

Allows a gas sprayed into the cuvette to be switched to an alternate gas (argon gas mixed with oxygen) to promote the decomposition of organic material at the ashing stage.

Interference with background and coexisting materials can be reduced by using argon gas that contains 5 to 10 % oxygen.

O Schematic of ashing process



GA Autosampler PEEK Nozzle

A nozzle tip made of PEEK* material, which does not bend easily. (Cannot be used with samples such as concentrated nitric acid, which dissolve PEEK)

 $\ensuremath{^{*}}$ "PEEK" is a registered trademark of VICTREX PLC UK in Japan and other countries.

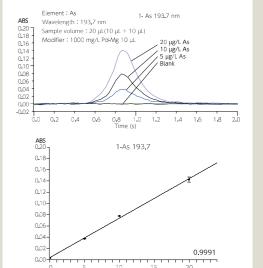


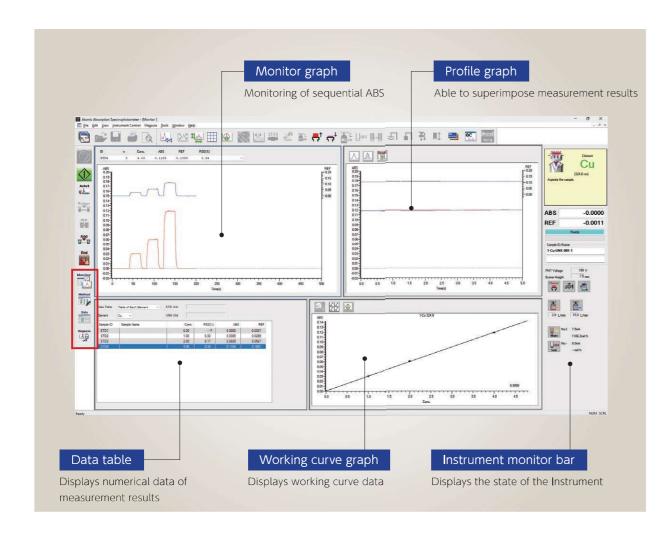
Pyro Tube DII HR

Makes it possible to more easily increase the sensitivity through injection of a larger volume of sample. This improves the efficiency of thermal conduction to the sample by dividing the sampling of the sample into two locations to increase the contact area with the cuvette. By doing this, the drying stage can be configured for a shorter period even in analysis of larger volume samples. This can reduce the analysis time by approximately 30% compared to using the concentrating function (comparison conducted by our company).



Measurement of arsenic standard solution





Wizard-based Parameter Settings ZA4000 ZA4800 ZA4700







Easy for Even Those New to the Analysis to Configure Parameters

→ Users can navigate between screens in order by clicking the icons to easily set the measurement parameters. Screens can be displayed directly by clicking the various icons.



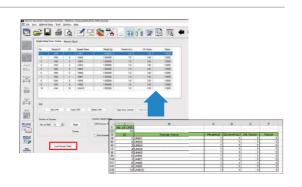


Load Sample Table Function

Names from Excel



Values can be imported from sheets created in Excel, allowing for the input of various data, such as "sample name", "weight", and "solvent". This is performed by the simple operation of clicking "Load Sample Table". This function is recommended for users who want to manage data using separate tables.



ZA4000 ZA4300 ZA4800 ZA4700



Monitor Screen

Displays analysis results data such as profiles and working curve on a single screen



Parameter Setting Screen

Wizard-based user-friendly parameter settings



Data Processing Screen

Viewing and editing measurement results saved by a single click during measurement



Automatic Device Diagnostics Function

Easily check wavelength precision, baseline stability, etc.

Diagnosis Function

ZA4000 ZA4300 ZA4800 ZA4700

Instrument State Can be Checked on the User Side

The wavelength precision, baseline stability, sensitivity, and reproducibility can be measured automatically, enabling the Instrument state to be diagnosed in a timely fashion.

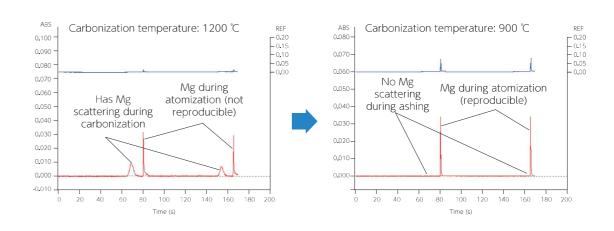
This is a convenient function for users who want to know the state of the instrument on a daily basis.

Continuous Monitoring

ZA4000 ZA4300 ZA4800 ZA4700

Batch Display of Atomizer Profiles

The absorbance and background signal are displayed as time elapses, making it possible to check for differences between samples at a glance. Regarding background measurement in particular, since background correction is applied even during the drying and ashing processes, the scattering of measurement elements can be monitored. The following diagram shows a profile confirming that magnesium is scattered at a ashing temperature of 1200 ° C. Scattering during ashing can be eliminated and absorbance with good reproducibility can be obtained by reducing the ashing temperature to 900 ° C. Users who want to configure the parameter settings in more detail can also consider the setting values from the drying and ashing background signals.





Hollow Cathode Lamps

ZA4000 ZA4300 ZA4800

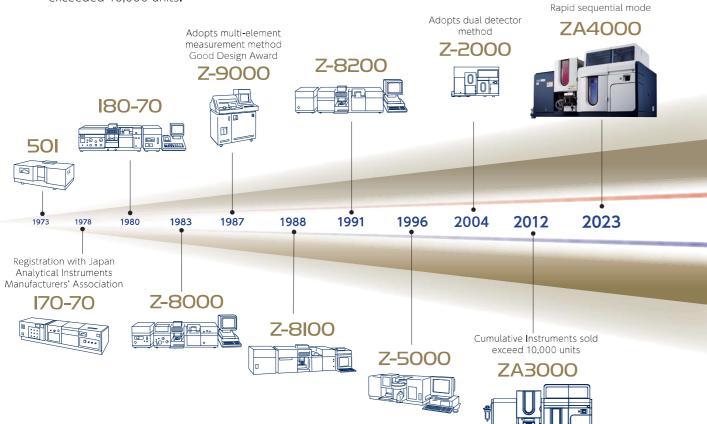
ZA4700

	Single element lamps								
Element symbol	Product name/ element name								
Ag	Silver	Со	Cobalt	K	Potassium	Pd	Palladium	Та	Tantalum
Al	Aluminum	Cr	Chromium	La	Lanthanum	Pt	Platinum	Te	Tellurium
As	Arsenic	Cu	Copper	Li	Lithium	Rh	Rhodium	Ti	Titanium
Au	Gold	Fe	Iron	Mg	Magnesium	Ru	Ruthenium	Tl	Thallium
В	Boron	Ga	Gallium	Mn	Manganese	Sb	Antimony	V	Vanadium
Ва	Barium	Ge	Germanium	Мо	Molybdenum	Sc	Scandium	W	Tungsten
Ве	Beryllium	Hf	Hafnium	Na	Sodium	Se	Selenium	Υ	Yttrium
Bi	Bismuth	Hg	Mercury	Nb	Niobium	Si	Silicon	Yb	Ytterbium
Ca	Calcium	In	Indium	Ni	Nickel	Sn	Tin	Zn	Zinc
Cd	Cadmium	Ir	Indium	Pb	Lead	Sr	Strontium	Zr	Zirconium

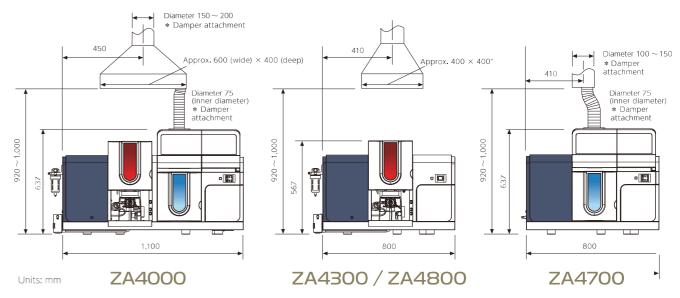
Multi-element lamp					
Ca-Mg	Cd-Pb	Cd-Zn	Cu-Fe-Ni	Fe-Mn-Ni	
Cu-Fe-Mn	Cr-Cu-Mn	Cu-Mn-Si	Cr-Cu-Fe-Mn-Ni	Co-Cr-Cu-Fe-Mn-Ni	

History of Polarized Zeeman Atomic Absorption Spectrophotometers

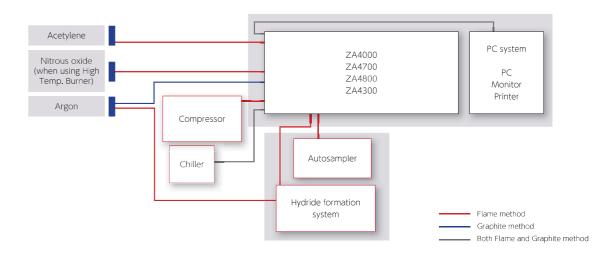
In 1978, Hitachi Limited led the world with the development of the 170-70 polarized Zeeman atomic spectrophotometer. Since then, many different series have been released and cumulative sales have exceeded 10,000 units.



Installation Conditions



Note: Use an installation table that can support the weight of not only the Instrument, but also the personal computer and printer.



	Cooling water	Diameter: 12 mm (outer diameter)
	Cooling Capacity	900 kcal / h or more
Water supply	Water flow rate	Water flow: 0.8 L /min (flame) Water flow: 2.0 L /min (graphite furnace)
/ Drain	Water pressure	35 to 150 kPa
	Water supply port	Within 4 m
	Water drain port	Height: 100 mm or less, aperture diameter: 50 mm or more
Gas supply	Argon	500 kPa
pressure*	Acetylene	90 kPa
(Set secondary	Nitrous oxide	400 kPa
pressure)	Air	500 kPa
Usage ten	nperature	15 to 35 ℃
Usage humidity		45 to 65% RH

Note: The gas cylinder should be installed in a gas cylinder bay, with piping connected from the gas cylinder bay to the installation location.

Duct		Material	Stainless steel			
	Dimensions		Approx. 600 (wide) × approx. 400 (deep) mm (ZA4000) [Here and in the next line, you could also just use the initial "Approx."]			
			Approx. 400 (wide) × approx. 400 (deep) mm (ZA4300 / ZA4800)			
			Diameter: 100 to 150 mm (ZA4700)			
	Suction power	Flame	600 to 1,200 m³/h (ZA4000)			
			600 to 1,200 m ³ /h (ZA4300 / ZA4800)			
		Graphite	10 to 25 m ³ /h (ZA4000)			
	Ο,	furnace	10 to 25 m ³ /h (ZA4700)			
	Model		Main unit			
Power supply	ZA4000		220/230/240 V \pm 5% 7.5 kVA (Power consumption under 4.1 kW) Single phase			
	ZA4300/ZA4800		115/220/230/240 V ± 10% 0.2 kVA (Power consumption under 0.1 kW) Single phase			
	ZA4700		220/230/240 V ± 5% 7.5 kVA (Power consumption under 4.1 kW) Single phase			

Note: Acetylene gas cylinders that use dimethylformamide (DMF) cannot be used as a solvent.

Note: Stainless steel piping with an inner diameter of 5 mm or more should be used for acetylene cylinders.

Note: A flashback arrestor device should be installed in the acetylene gas piping. (High Pressure Gas Safety Act)

Note: If the water pressure of the cooling water exceeds 150 kPa, provide and install a pressure reducing valve.

Note: It is recommended that a cooling water recirculation unit be installed in the cooling water supply equipment.

	ite furnace absorption
Measurement method Background correction method Polarized Zeeman correction method Polarized Zeeman correction method Polarized Zeeman correction method	absorption
Background correction method Polarized Zeeman correction method Replace sample chamber Atomizer unit does not need to	
Replace sample chamber Atomizer unit does not need to	
Illove	
Mount/diffraction grating Czerny-Turner mount / 1,800 lines/mm, 200 nm blaze	
Wavelength range/setting method 190 to 900 nm / Automatic spectral peak setting	
Focal length, reciprocal dispersion 400 mm / 1.3 nm/mm	
Slit width 4 settings (0.2, 0.4, 1.3, 2.6 nm)	
Detector Photomultiplier tube × 2	
simultaneously/ simultaneously/ simultaneously/ simultaneously/	et method) 2 alight taneously/ mean current value)
Magnet for Zeeman effect 0.9 T permanent magnet *1	_
Burner Premixed fishtail type	_
Burning condition setting Automatic flow rate setting of combustion gas	
Burner Premixed fishtail type Burning condition setting Automatic flow rate setting of combustion gas Optical flame monitoring, flame sensor error detection, fuel/auxiliary gas pressure monitoring, drain liquid monitoring, free value from the cooling water flow monitoring, flash-back shock absorption, safety fire extinguishing at power failure (buffer tankmethod), flow stop check at flame turnoff, prevention of restart at reconnection of power, N2O select safety mechanism	_
Magnet for Zeeman effect 1.0 T permanent magnet *1 1.0 T permanent magnet *1	anent magnet *1
Temperature control 50 to 2,800 °C, overcurrent prevention Clean stage only: 50 to 2,900 °C Clean stage on (Pyrotube C III-R, pyrotube D III-R) (Pyrotube T III-R) (Pyrotube T III-R) (Pyrotube T III-R)	overcurrent prevention nly: 50 to 2,900 °C HR, pyrotube D IIHR]
Heating current control Optical temperature control	re control/fixed current ontrol
Gas flow rate control Sheath gas: Argon gas 3 L/min Carrier gas: Argon gas Carrier gas: Argon gas	Argon gas 3 L/min (as: Argon gas 0 mL/min (4 values)
Safety monitoring function Argon gas pressure monitoring/cooling water flow monitoring/ heating furnace temperature monitoring heating furnace temperature monitoring	ire monitoring/cooling w monitoring/ emperature monitoring
Number of sample containers 60 (1.5 mL container) or 96 microplate (optional accessory) 60 (1.5 mL container) or 96 microplate (optional accessory)	L container) or (optional accessory)
Number of sample containers 96 microplate (optional accessory) Autosampler sample divided injection each sample/ sequential divided injection Sample injection volume Sample injection speed Selectable from 5 values Applicable solvents Aqueous solution, ethanol, methanol, actone, MIBK Carry over 10° or less (with aqueous solution standard sample) Heated injection function Capable Concentration (inside furnace)/ Concentration (inside furnace)/ Local Stimes (Alb 10 times)	each sample/sequential d injection
Sample injection volume 1 to 100 μL	ο 100 μL
Selectable from 5 values Selectable	e from 5 values
Applicable solvents Aqueous solution, ethanol, methanol, acetone. MIBK Aqueous solution acetone. MIBK	n, ethanol, methanol, one, MIBK
Carry over 10° or less (with aqueous solution standard sample) 10° or less (with aqueous solution standard sample) 10° or less (with aqueous solution standard sample)	th aqueous solution ard sample)
Heated injection function Capable Ca	apable
Concentration (inside furnace) / 1 to 25 times / 1 to 10 times 1 to 25 times /	es / 1 to 10 times
Personal computer OS: Windows® 11 Pro, 64-bit edition *2	
Signal type Zeeman AA, sample, reference, and emission intensity	
Working curve Standard sample: Maximum 10 points/Working curve creation: Least squares method and Newton's method approximation formula: 3 types/sensitivity standard addition method/simplified standard addition method *9	
Personal computer Signal type Signal type Working curve Standard sample: Maximum 10 points/Working curve creation: Least squares method and Newton's method approximation formula: 3 types/sensitivity standard addition method/simplified standard addition method or sample in the processing of the processing baseline correction/statistical calculations (mean value, standard deviation, relative standard adrition method/simplified standard addition method or sample blank processing/2rer point correction of calibration curve/ baseline correction/statistical calculations (mean value, standard deviation, relative standard error, correlation function)/detection limit measurement processing time region specification Quality Control function Sample check (detection limit), STD check, QC sample check, calibration curve check, recovery check analysis parameters/save analysis parameters, analysis results, measurement signal/reference signal, device operational status/error data, error	~
Quality Control function Sample check (detection limit), STD check, QC sample check, calibration curve check, recovery chec	
results/help function message display, analysis data	ror recovery process
Main unit (w) × (D) × (H)/Mass	637 mm/137 kg
Power supply 50/60Hz 50/60Hz 50/60Hz 50	240V, 7.5kVA, /60Hz
Power consumption 4.1 kW or less 0.1 kW or less 4.1 kV	W or less

 $\boldsymbol{\ast}$ This product is not approved as a medical device under the Pharmaceutical Affairs Law.

*1 Users who have a pacemaker should not come within 1 m of this instrument, and should not handle the instrument.

*2 Windows® is registered trademark of Microsoft Corporation in the USA and other countries.

*3 Standard addition method and simple standard addition method are not available in Rapid Sequential mode on ZA4800.



*This logo is a registered trademark of Hitachi High-Tech Corporation in the US, the EU, the UK, China, Korea, Taiwan and Japan.

CAUTION: For correct operation, follow the instruction manual when using the instrument.

Specifications in this catalog are subject to change with or without notice, as Hitachi High-Tech Science Corporation continues to develop the latest technologies and products for its customers.

NOTICE: The system is For Research Use Only, and is not intended for any animal or human therapeutic or diagnostic use. These data are an example of measurement; the individual values cannot be guaranteed.

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